Overview

Peristaltic Pumps: An Open Loop Flow Control System

Chemical Mechanical Planarization (CMP) systems can utilize an open-loop, peristaltic pump control system for delivering slurry to the point-of-use polishing pads (see figure 1). In many cases, the polishing system flow rate is not directly measured or properly controlled, causing performance, maintenance and accuracy issues. Fluctuations of slurry flow occur due to changes in supply pressure, the gradual deterioration of the peristaltic pump flexible tubing and other factors. As a result, most fabs report 10–20% slurry fluid flow fluctuation as well as occasional no flow conditions that can lead to dry polish and catastrophic wafer loss.

Performance Considerations

Defects
Too little or too much slurry flow may lead to overpolishing or underpolishing, decreasing overall yield rates.

Accuracy
Inconsistent slurry flow rate to the polishing pad due to variable facility supply pressure, resulting in process downtime, excessive slurry use and flow rate variations of 10–20%.

Chemical Consumption
Using peristaltic pumps, many fabs use excess slurry flow to ensure that the minimum slurry flow is maintained, resulting in valuable slurry loss and chemical waste.

Yield
Wafer scrap and loss due to catastrophic failure from the lack of feedback alarms on original manufactured CMP equipment.

Contamination
Peristaltic pump tubing degradation and wear, resulting in particle shedding of the soft polymer tubing material and becomes a source for wafer defects.

Maintenance
Pump repair and replacement time and costs, including tubing replacement and calibration issues.

Flow Variation Causes

Fluid flow fluctuations affect accuracy, yield, defects, chemical consumption, contamination and maintenance. The factors that cause fluctuations in slurry flow from peristaltic pumps include:

- Changes in supply pressure
- Tubing degradation

Figure 1. Typical open-loop peristaltic control system

[Diagram of typical open-loop peristaltic control system]
Figure 2. Flow rate varies due to inlet pressure changes while the peristaltic pump operates at constant speed.

Changes In Supply Pressure

Figure 2 illustrates the instantaneous variation of fluid flow due to inlet pressure changes while a peristaltic pump operates at a constant speed. Notice the variation from the target flow rate.

In turn, these pumps require frequent calibration to correlate flow rate and pump speed, while flow of slurry to the polishing pad may vary as much as 10–20% due to variations in facility operating pressures.

Figure 3. Flow rate varies due solely to peristaltic pump tubing wear while the pump speed and feed pressure remain constant.

Tubing Degradation

Figure 3 illustrates the long term deterioration of the fluid flow due solely to gradual deterioration and deformation of the peristaltic pump tubing flexible during the first 30+ hours of use. The pump speed and feed pressure remained constant during the 30+ hours of operation.

The Solution: A Closed-Loop Flow Control System

Installing a closed-loop flow control system enables users to increase the reliability and performance of the CMP slurry delivery system and process tool overall performance.

Using an automated flow control system with direct flow and pressure measurements provides the following advantages:

- Eliminates the need for frequent pump calibrations and increases tool uptime
- Maintains a constant flow of slurry to the polishing pad at the desired flow rate
- Allows for process optimization during each process step by controlling slurry flow
- Provides process alarms for low- or no-flow conditions
- Provides process alarms for low inlet pressure
- Minimizes slurry, chemical and DI water waste

NT Integrated Flow Controllers.

NT Integrated Flow Controller – Closed Loop Control System

The NT Integrated Flow Controller uses direct flow and pressure measurement for automated dispense control. It comprises three sub-components: a differential pressure flowmeter with no moving parts, a stepper motor actuated diaphragm control valve that minimizes movement, and control software that regulates valve position based on the desired flow and actual flow conditions.
The flow controller receives the same control signal that is used to control the peristaltic pump, thus the process upgrade is easy to perform and is not intrusive.

Without manual calibration, the NT Integrated Flow Controller achieves the desired flow rate at the user’s flow setpoint during inlet pressure changes (see figure 4). The unit has 1% full scale flow accuracy and response time to setpoint changes or feed pressure changes within <3 seconds.

![Figure 4. Flow rate is controlled within a three-second response time despite significant changes in feed pressure.](image)

![Figure 5. Close-up of one transition point from figure 4.](image)

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